

# Dynamics of $\alpha$ - and $\beta$ -processes in thin polymer films: poly(vinyl acetate) and poly(methyl methacrylate)

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(Received May 9, 2001)

Dynamics of thin films of poly(vinyl acetate) (PVAc) and poly(methyl methacrylate) (PMMA) have been investigated by dielectric relaxation spectroscopy in the frequency range from 0.1Hz to 1MHz at temperatures from 263K to 423K. The  $\alpha$ -process, the key process of glass transition, is observed for thin films of PVAc and PMMA as a dielectric loss peak at a temperature  $T_\alpha$  in temperature domain with a fixed frequency. For PMMA the  $\beta$ -process is also observed at a temperature  $T_\beta$ . For PVAc,  $T_\alpha$  decreases gradually with decreasing thickness, and the thickness dependence of  $T_\alpha$  is almost independent of the molecular weight ( $M_w \leq 2.4 \times 10^5$ ). For PMMA,  $T_\alpha$  remains almost constant as thickness decreases down to a critical thickness  $d_c$ , at which point it begins to decrease with decreasing thickness. Contrastingly,  $T_\beta$  decreases gradually as thickness decreases to  $d_c$ , and below  $d_c$  it decreases drastically. For both PVAc and PMMA, the broadening of the distribution of the relaxation times in thinner films is observed and this broadening is more pronounced for the  $\alpha$ -process than for the  $\beta$ -process. It is also observed that the relaxation strength is depressed as the thickness decreases for both the polymers.

PACS numbers: 64.70.Pf, 68.60.-p, 77.22.Gm

## I. INTRODUCTION

Recent progress in theoretical and experimental studies has clarified many properties of glass transitions [1,2]. However, the mechanism of the glass transition has not yet been fully understood [3]. The major issue is the experimental approach to the investigation of the length scale of the glass transition and dynamics of the  $\alpha$ -process such as dynamical heterogeneity [4,5]. According to the Adam and Gibbs theory, the dynamics of glass transitions are associated with cooperative motions which are characterized by a so-called *cooperatively rearranging region* (CRR), in which molecules move cooperatively with each other [6]. The size of the CRR is assumed to increase as temperature decreases to the glass transition temperature  $T_g$ . The characteristic length scale associated with such cooperative motions has been investigated by multi-dimensional NMR [7], dielectric hole burning [8] and photobleaching [9] for bulk systems. Another approach to studying the length scale is the investigation of the finite size effect on glass transition dynamics through confined systems such as thin polymer films [10] or small molecules in nanopores [11].

The first direct measurement of the reduction in  $T_g$  in thin polymer films has been made by Keddie *et al.* in 1994 [12]. In their work, the film thickness of the thin films of polystyrene (PS) supported on a hydrogen passivated silicon wafer has been measured as a function of temperature by an ellipsometer. The results showed that the observed  $T_g$  in such thin films can be described as a function of film thickness,  $d$ , as follows:

$$T_g(d) = T_g^\infty \left[ 1 - \left( \frac{A}{d} \right)^\delta \right], \quad (1)$$

where the best-fit parameters are  $T_g^\infty = 373.8\text{K}$ ,  $A = 1.3 \pm 0.1\text{nm}$ , and  $\delta = 1.28 \pm 0.20$  [13]. The molecular weight ( $M_w$ ) dependence of  $T_g(d)$  has not been observed for  $M_w$  range from  $1.2 \times 10^5$  to  $2.9 \times 10^6$ , and hence it was concluded that the confinement effect of polymer chains within thin layers may be neglected in such systems. Further measurements of  $T_g$  in thin films of poly(methyl methacrylate) (PMMA) supported on two different kinds of substrate revealed that the strong attractive interactions between substrate and polymers lead to increase in  $T_g$  with decreasing film thickness [14].

In order to remove such interactions between substrate and polymers, Forrest *et al.* measured  $T_g$  for *freely standing films* of polystyrene by Brillouin light scattering measurements [15,16]. They obtained the thickness dependence of  $T_g$  as follows:

$$T_g(d) = \begin{cases} T_g^\infty \left( 1 - \frac{d_0 - d}{\zeta} \right) & : d < d_0 \\ T_g^\infty & : d > d_0, \end{cases} \quad (2)$$

where  $T_g^\infty$  is the glass transition temperature for thick films,  $\zeta$  is the constant and  $d_0$  is the critical thickness. The critical thickness  $d_0$ , below which  $T_g$  decreases linearly with decreasing film thickness, depends on the molecular weight, *i.e.*,  $d_0$  increases with the molecular weight in a way similar to the radius of gyration of polymer chains.

In our previous papers, we performed electric capacitance measurements for thin films of polystyrene supported on Al-deposited glass substrate and determined

the  $T_g$  as a temperature at which the temperature dependence of capacitance changes discontinuously [17,18]. As a result, we confirmed the reduction of  $T_g$  in our system in a way similar to Eq.(1). Furthermore, we made volume relaxation measurements on thin polystyrene films and measured the temperature  $T_\alpha$  at which the imaginary component of complex thermal expansion coefficient has a peak at a given very low frequency corresponding to the relaxation time about 100 sec during the heating process of a constant rate [19,20]. The temperature  $T_\alpha$  thereby obtained can be regarded as the glass transition temperature  $T_g$ . In our measurements it is found that  $T_g$  decreases slightly with decreasing film thickness down to a critical thickness  $d_c$ , and below  $d_c$  it decreases very rapidly. The value of  $d_c$  changes with  $M_w$  in the similar way to the radius of gyration of polymer chains. This behavior of  $T_g$  is quite similar to those obtained in freely standing films as shown in Eq.(2) except the slight change in  $T_g$  above  $d_c$ .

Intensive investigations have been performed so far mainly on polystyrene films [10]. It is important to clarify whether the results extracted from the investigations on thin polystyrene films hold also for other polymers. In this paper, therefore, we investigate the dynamics of thin films of poly(vinyl acetate)(PVAc) and PMMA by dielectric relaxation spectroscopy. PVAc is a polymer suitable for dielectric relaxation measurements because a monomer unit of PVAc has a large dipole moment [21]. In PMMA, there is a strong  $\beta$ -process which is due to the hindered rotation of the side group in addition to the  $\alpha$ -process [21]. It is indispensable to investigate the size dependence of dynamics of the  $\alpha$ -process and the  $\beta$ -process when elucidating the nature of glass transition.

This paper consists of five sections. After the introduction, experimental details on preparation method of thin films and dielectric relaxation spectroscopy are given in Sec.II. In Sec.III, experimental results on poly(vinyl acetate) and poly(methyl methacrylate) by dielectric relaxation spectroscopy are shown. In particular, thickness dependence of the temperatures  $T_\alpha$  and  $T_\beta$  corresponding to the  $\alpha$ - and  $\beta$ -peaks in the dielectric loss and the width of the distribution of the relaxation time of the  $\alpha$ - and  $\beta$ -processes are focused in Sec.III. Discussions on the present experimental results compared with the results reported previously are given in Sec.IV and a summary is given in Sec.V.

## II. EXPERIMENTS

The polymer samples used in this study (PVAc and PMMA) are purchased from Scientific Polymer Products, Inc. The molecular weight and radius of gyration of the polymers are listed in Table I. The glass transition temperatures of PVAc and PMMA in the bulk states are 303K and 373K, respectively. Thin polymer films were prepared by spin-coating a toluene solution of PVAc (PMMA) onto Al-deposited glass substrate. Film thick-

ness is controlled by changing the concentration of the solution. The thin films obtained by spin-coat method were annealed *in vacuo* for 48 hours at 303K for PVAc and 353K for PMMA, respectively. After annealing, Al was vacuum-deposited once more onto the thin films to serve an upper electrode.

Dielectric measurements were performed by using an LCR meter (HP4284A) for the frequency range from 20Hz to 1MHz and an impedance analyzer (Solartron Instruments SI1260) for the frequency range from 0.1Hz to 1MHz. The temperature of a sample cell was changed between 273K and 373K for PVAc and between 263K and 423K for PMMA at a constant rate of 0.5K/min. The dielectric measurements during the heating and cooling processes were performed repeatedly several times. Data acquisition was made during the above cycles except the first cycle. The good reproducibility of dielectric data was obtained after the first cycle.

The thickness  $d$  is related to the electric capacitance  $C'$  of thin films in the following way:  $C' = \epsilon' \epsilon_0 \frac{S}{d}$ , where  $\epsilon_0$  is the permittivity of the vacuum,  $\epsilon'$  is the permittivity of the polymer (PVAc or PMMA) and  $S$  is the effective area of the electrode ( $S=8.0\text{mm}^2$ ). For the frequency range where there are no contributions due to any dielectric dispersion,  $\epsilon'$  can be regarded as constant for any change in frequency, and hence the film thickness is inversely proportional to the electric capacitance. Relative film thickness at a given temperature can be obtained from the electric capacitance of the thin films at a frequency within the above frequency range. The frequency and the temperature we chose for the determination of the relative thickness are 8kHz and 298K for PVAc, and 1kHz and 273K for PMMA. The absolute values of the film thickness for several films were measured directly by an atomic force microscope (Shimadzu SPM-9500) in order to calibrate the film thickness.

As shown in a previous paper [18], the resistance of the Al electrodes cannot be neglected for dielectric measurements of very thin films. This resistance leads to an artifact loss peak on the high frequency side; this peak results from the fact that the system is equivalent to a series circuit of a capacitor and resistor [23]. Because the peak shape in the frequency domain is described by a Debye-type equation, the "C-R peak" can easily be subtracted. The data thus corrected were used for further analysis in the frequency domain.

## III. RESULTS

### A. Poly(vinyl acetate)

#### 1. Dielectric relaxation of the $\alpha$ -process in PVAc

Figure 1 shows the dependence of the complex electric capacitance ( $C^* = C' - iC''$ ) on the logarithm of frequency at various temperatures for thin films of PVAc

with  $M_w=1.8 \times 10^5$  and film thicknesses (a)  $d=440\text{nm}$  and (b)  $d=16\text{nm}$ . In this figure, we find that the imaginary component  $C''$  has a peak due to the  $\alpha$ -process. The peak frequency shifts to the higher frequency side as temperature increases. Comparing Fig.1(a) and Fig.1(b), we find that the peak position shifts to the higher frequency side at a fixed temperature as the film thickness decreases from 440nm to 16nm.

The temperature change in the dielectric loss at 100Hz normalized with the peak value for the bulk sample is shown in Fig.2 in the case of PVAc with  $M_w=1.8 \times 10^5$ . The dielectric peak due to the  $\alpha$ -process possesses a maximum at the temperature  $T_\alpha$ . It is found in Fig.2 that the temperature  $T_\alpha$  decreases with decreasing film thickness. At the same time the peak width of the  $\alpha$ -process increases and the height at  $T_\alpha$  decreases with decreasing film thickness. This behavior is related to the change in the distribution of the relaxation times and the relaxation strength with the film thickness.

Figure 3 displays the temperature dependence of the frequency  $f$  of the  $\alpha$ -process for thin films of PVAc with three different thicknesses 440nm, 62nm, and 18nm, where  $f$  is associated with a characteristic time of the  $\alpha$ -process  $\tau_\alpha$  via the relation  $2\pi f\tau_\alpha=1$ . Each point in Fig.3 consists of a data set  $(1/T_\alpha, \log_{10} f)$ . For each film thickness, the temperature dependence of  $\tau_\alpha$  can well be reproduced by the Vogel-Fulcher-Tammann (VFT) law [24]:  $\tau_\alpha(T) = \tau_\alpha^\infty \exp[U/(T - T_0)]$ , where  $\tau_\alpha^\infty$  is the relaxation times at very high temperatures,  $U$  is the apparent activation energy, and  $T_0$  is the Vogel temperature. At a given temperature, the frequency  $f$  increases with decreasing film thickness, *i.e.*, the relaxation becomes faster in thinner films. This thickness dependence of  $f$  (and  $\tau_\alpha$ ) becomes stronger as the temperature approaches the glass transition temperature. This behavior is quite similar to that observed in thin films of PS supported on glass substrate [17,18].

In order to check how the  $\alpha$ -process changes with film thickness, the thickness dependence of the temperature  $T_\alpha$  at the frequency 100Hz is shown in Fig.4 for three different molecular weights  $1.2 \times 10^5$ ,  $1.8 \times 10^5$  and  $2.4 \times 10^5$ . The error bars in Fig.4 stand for the standard deviation in  $T_\alpha$  for the data acquired by measurements done repeatedly several times. Because the glass transition temperature  $T_g$  can be regarded as the value of  $T_\alpha$  obtained for a very low frequency of the applied electric field, for example,  $f \approx 1/(2\pi \cdot 10^2 \text{ sec})$ , the absolute value of  $T_g$  is lower than that of the  $T_\alpha$  for  $f=100\text{Hz}$ . However, it is possible to extract qualitative information on the thickness dependence of  $T_g$  from the observed thickness dependence of  $T_\alpha$  in Fig.4.

The solid curve in Fig.4 is obtained by using the same form of Eq.(1) in which  $T_g$  is replaced by  $T_\alpha$  with parameters as follows:  $T_\alpha^\infty=334.3 \pm 0.1\text{K}$ ,  $A = 0.11 \pm 0.03\text{nm}$ ,  $\delta = 0.77 \pm 0.04$ . Because the single curve can reproduce the observed values of  $T_\alpha$  for the three different molecular weights, the temperature  $T_\alpha$  seems to have almost no  $M_w$  dependence and hence we conjecture that  $T_g$  is also

independent of the molecular weight for  $M_w=1.2 \times 10^5$ - $2.4 \times 10^5$  and  $d > 10\text{nm}$ .

In order to discuss the dynamics of the  $\alpha$ -process in thin films of PVAc, the observed complex dielectric constant  $\epsilon^*(\omega)$  in Fig.1 is fitted to the following model function:

$$\epsilon^*(\omega) = \epsilon_\infty + A\omega^{-m}e^{-i\frac{\pi}{2}m} + \frac{\Delta\epsilon}{(1 + (i\omega\tau_0)^{\alpha_{\text{HN}}})^{\beta_{\text{HN}}}}, \quad (3)$$

where  $\omega = 2\pi f$  and  $\epsilon_\infty$  is the permittivity at a very high frequency. The second term in the r.h.s. is a contribution from space charge [25], and it can be attributed to pure DC conductivity if  $m = 1$ . In the case of PVAc, the fitted value of  $m$  was found to be between 0.40 and 0.93 depending on film thickness. The third term in the r.h.s. comes from the  $\alpha$ -process and its form is empirically proposed by Havriliak-Negami [26], where  $\Delta\epsilon$  is the relaxation strength,  $\tau_0$  is the characteristic time,  $\alpha_{\text{HN}}$  and  $\beta_{\text{HN}}$  are the shape parameters.

The thickness dependence of the relaxation strength  $\Delta\epsilon$  obtained from the observed values of  $\epsilon^*(\omega)$  at 333K is shown in Fig.5 for thin films of PVAc with  $M_w=2.4 \times 10^5$ , where  $\Delta\epsilon$  is normalized with respect to the value of  $\Delta\epsilon$  for the bulk sample (See open circles). The temperature 333K was chosen because the dielectric loss peak of the  $\alpha$ -process is located at the center of the frequency window in the present measurement at this temperature. As the film thickness decreases, the normalized relaxation strength decreases from 1 to about 0.2. This behavior in relaxation strength corresponds to the decrease in the height at  $T_\alpha$  in dielectric loss in Fig.2. The  $d$  dependence of  $\Delta\epsilon$  will be discussed later. The fitting parameters  $\alpha_{\text{HN}}$  and  $\beta_{\text{HN}}$  of the HN equation are shown in Fig.6. It is found that with decreasing film thickness the parameter  $\alpha_{\text{HN}}$  decreases and  $\beta_{\text{HN}}$  slightly increases. The decrease in  $\alpha_{\text{HN}}$  with decreasing film thickness implies the broadening of the distribution of the relaxation times.

## 2. Distribution of the relaxation times

The experimental observation that the  $\epsilon^*(\omega)$  does not obey a simple Debye equation but rather a complicated HN equation can be accounted for by assuming that  $\epsilon^*(\omega)$  is expressed as the sum of the Debye equations with different relaxation times in the following way:

$$\epsilon^*(\omega) = \epsilon_\infty + \Delta\epsilon \int_{-\infty}^{+\infty} \frac{F(\log_e \tau) d(\log_e \tau)}{1 + i\omega\tau}, \quad (4)$$

where the second term in Eq.(3) is omitted.  $F(s)$  is a distribution function of the logarithm of the relaxation times of the  $\alpha$ -process ( $s = \log_e \tau$ ) and is normalized as follows:  $\int_{-\infty}^{+\infty} F(s) ds = 1$ . If it is assumed that  $\epsilon^*(\omega)$  is expressed by the HN equation, the analytical form of  $F(s)$  can easily be obtained in the following way with the parameters  $\alpha_{\text{HN}}$ ,  $\beta_{\text{HN}}$ , and  $\tau_0$ :

$$F(s) = \frac{1}{\pi} (1 + 2e^{\alpha_{\text{HN}}(x_0-s)} \sin \pi \alpha_{\text{HN}} + e^{2\alpha_{\text{HN}}(x_0-s)})^{-\beta_{\text{HN}}/2} \times \sin \left[ \beta_{\text{HN}} \tan^{-1} \left( \frac{e^{\alpha_{\text{HN}}(x_0-s)} \sin \pi \alpha_{\text{HN}}}{1 + e^{\alpha_{\text{HN}}(x_0-s)} \cos \pi \alpha_{\text{HN}}} \right) \right], \quad (5)$$

where  $x_0 = \log_e \tau_0$ .

Figure 7 displays the distribution of  $\log_{10} \tau_\alpha$  calculated in terms of Eq.(5) with the parameters  $\alpha_{\text{HN}}$ ,  $\beta_{\text{HN}}$  and  $\tau_0$  at 333K for thin films of PVAc with  $M_w=2.4 \times 10^5$  and  $d=1400\text{nm}$  and  $19\text{nm}$ . In this figure, it is found that the average relaxation time of the  $\alpha$ -process decreases with decreasing film thickness, and that the width of the distribution of the relaxation times  $\tau_\alpha$  becomes broader in thinner films. In order to quantify the change in the distribution of  $\tau_\alpha$ , the full width  $w$  at the half maximum (FWHM) at 333K of  $F(s)$  was evaluated as shown in Fig.8(a) for thin films of PVAc with  $M_w=2.4 \times 10^5$  (See open circles). It is found that the width  $w$  increases with decreasing film thickness. The thickness dependence of  $w$  is given by the equation  $w(d) = w_0(1 + a/d)$ , where  $w_0=0.92 \pm 0.03$  and  $a=22.0 \pm 1.6\text{nm}$  for the  $\alpha$ -process of PVAc. This broadening of the distribution of the relaxation times and its functional form have also been observed in thin films of polystyrene by dielectric relaxation spectroscopy [18] and ellipsometric measurements [27].

## B. Poly(methyl methacrylate)

### 1. Temperature dispersion of dielectric loss

Figure 9 shows the temperature change in the imaginary part of the complex dielectric constant at a fixed frequency for PMMA with  $M_w=4.9 \times 10^5$  and  $d=900\text{nm}$  and  $9.5\text{nm}$ . The value of  $\epsilon''$  is normalized with the maximum value for the bulk sample ( $d=900\text{nm}$ ). The value  $\epsilon''$  at a fixed frequency (40Hz) displays an anomalous increase with temperature due to the  $\alpha$ - and  $\beta$ -processes, and it possesses two maxima at the temperatures  $T_\alpha$  and  $T_\beta$ . The values of  $T_\alpha$  and  $T_\beta$  depend not only on the frequency  $f$  but also on the film thickness, as we can see in Fig.9; in the case of  $f=40\text{Hz}$ ,  $T_\alpha=401\text{K}$  and  $T_\beta=320\text{K}$  for  $d=900\text{nm}$ , and  $T_\alpha=383\text{K}$  and  $T_\beta=301\text{K}$  for  $d=9.5\text{nm}$ . Both the height and the width of the  $\beta$ -peak are larger than those of the  $\alpha$ -peak. The origin of the  $\alpha$ -process is attributed to the micro-Brownian motion of the polymer main chain, while that of the  $\beta$ -process is to the hindered rotation of the side branch of PMMA [21].

In order to extract the peak temperatures  $T_\alpha$  and  $T_\beta$  and the widths  $\Delta T_\alpha$  and  $\Delta T_\beta$ , the observed values  $\epsilon''$  as a function of temperature were fitted by the sum of the two Lorentzian functions  $\tilde{\epsilon}_i'' / \{1 + [(T - T_i)/\Delta T_i]^2\}$  ( $i = \alpha, \beta$ ). The functional form has no physical meaning, but it is used only to obtain the peak temperature and the width. If necessary, the contribution due to DC conductivity was also taken into account by adding another peak at higher temperature to the fitting function.

The thickness dependence of the widths of the  $\alpha$ - and  $\beta$ -processes in the temperature domain, normalized with those in the bulk sample,  $\Delta T_i/\Delta T_i^0$ , is shown in Fig.8(b), where  $\Delta T_i^0$  is the width for the bulk sample. The solid lines in Fig.8(b) are given by  $\Delta T_i(d) = \Delta T_i^0(1 + a/d)$ . In PMMA,  $\Delta T_\alpha^0 = 7.9 \pm 0.5\text{K}$  and  $a = 16.7 \pm 2.0\text{nm}$  for the  $\alpha$ -process and  $\Delta T_\beta^0 = 48.4 \pm 0.9\text{K}$  and  $a = 1.3 \pm 0.3\text{nm}$  for the  $\beta$ -process.

The dependence of the frequency  $f$  on the reciprocal of the temperatures  $T_\alpha$  and  $T_\beta$  is shown in the dispersion map of Fig.10 for PMMA with  $M_w=4.9 \times 10^5$  with three different film thicknesses. The number of data points of the  $\alpha$ -process is limited because the small  $\alpha$ -peak merges with the large  $\beta$ -peak as the frequency increases, and as a result it is much more difficult to extract  $T_\alpha$  at higher frequencies.

As shown in Fig.10, the branch of the  $\beta$ -process is well separated from that of the  $\alpha$ -process for the frequency range below about 500Hz. However, the  $\beta$ -process approaches the  $\alpha$ -process as the frequency or the temperature increases, because the slope of the straight line corresponding to the  $\beta$ -process is much smaller than that of the  $\alpha$ -process: the corresponding apparent activation energies in this frequency range are  $651 \pm 6\text{ kJ/mol}$  for the  $\alpha$ -process and  $32.7 \pm 0.2\text{ kJ/mol}$  for the  $\beta$ -process. In this limited frequency range investigated here, thickness dependence of the apparent activation energy can not be observed. (Here, it should be noted that the  $\alpha$ -branch can indeed be fitted by a straight line in Fig.10, because of the limitation of the frequency range, but we do not intend to deny the validity of the VFT law.) In Fig.10 we find that both the  $\alpha$ - and  $\beta$ -processes shift to the higher frequency side at a fixed temperature, as the thickness decreases, *i.e.*, both the relaxations become faster.

### 2. $T_\alpha$ and $T_\beta$ as a function of thickness

In order to quantify the thickness dependence of  $T_\alpha$  and  $T_\beta$ , the frequency is fixed to be 40Hz and the temperatures  $T_\alpha$  and  $T_\beta$  are evaluated from the observed curve of  $\epsilon''$  vs.  $T$  for various film thicknesses from 9.5nm to 1000nm. The results are summarized in Fig.11, where Figs. 11(a) and (b) display the thickness dependence of the temperatures  $T_\alpha$  and  $T_\beta$  observed at 40Hz for the thin films of PMMA with  $M_w=4.9 \times 10^5$ , respectively.

Figure 11(a) shows that  $T_\alpha$  remains almost constant within the experimental accuracy as the film thickness decreases down to a critical thickness  $d_{\alpha,c}$ , at which point  $T_\alpha$  begins to decrease rapidly with  $d$ . The solid curve in Fig.11(a) below  $d_{\alpha,c}$  is given by a linear relation between  $T_\alpha$  and  $d$ , although it does not appear to be a straight line because of the logarithmic scale of the horizontal axis. The amount of the depression of  $T_\alpha$  in the thin films is about 20K between the bulk sample and the thinnest film with  $d=9.5\text{nm}$ . In this case, the critical thickness  $d_{\alpha,c}$  is found to be about 20nm for the  $\alpha$ -process at 40Hz.

On the other hand, thickness dependence of  $T_\beta$  seems to be to some extent different from that of  $T_\alpha$ , as shown in Fig.11(b). The temperature  $T_\beta$  decreases slightly with decreasing film thickness down to a critical thickness  $d_{\beta,c}$  even for the relatively thick films. Below a critical thickness  $d_{\beta,c}$ ,  $T_\beta$  decreases more rapidly with decreasing film thickness. The depression in  $T_\beta$  is about 25K also in this case for the thickness range investigated here, and the critical thickness  $d_{\beta,c}$  is about 19nm. It is quite interesting that the critical thickness of the  $\beta$ -process almost agrees with that of the  $\alpha$ -process;  $d_{\alpha,c} \approx d_{\beta,c} (\equiv d_c)$ . This result may suggest that there is a strong correlation between the  $\alpha$ -process and the  $\beta$ -process, although the two processes at 40Hz exist quite separately on the dispersion map in Fig.10.

In order to investigate the dynamical behavior in thin films of PMMA with  $d=900\text{nm}$  and  $9.5\text{nm}$ , we observed the frequency dependence of the complex dielectric constant at a fixed temperature, as shown in Fig.12. Corresponding to Fig.9, the large peak due to the  $\beta$ -process can be seen in the  $C''$  vs.  $f$  plot and a small contribution from the  $\alpha$ -process can also be observed at the foot of the large  $\beta$ -peak at 403K. According to the procedure of data analysis done for PVAc, the observed  $C''$  is fitted to a model function consisting of the two HN functions. In Fig.12, the calculated values with this model function are shown as solid curves. For thick films, the model function can very well reproduce the observed results for the temperature and frequency range shown in Fig.12. For very thin films, the data at higher frequency (above  $10^4$  Hz) include relatively large errors. Therefore, in such a case, we used the data below  $10^4$  Hz for the data fitting.

In order to evaluate the distribution  $F(s)$  and the relaxation strength  $\Delta\epsilon$ , the fitting parameters were obtained for the  $\beta$ -process at the temperature at which the  $\beta$ -peak is located at 300Hz for various film thicknesses. In this case, because the temperatures are located between 323 K and 338 K depending on the film thickness, the contribution from the  $\alpha$ -process can safely be neglected. Using the parameters  $\alpha_{\text{HN},\beta}$ ,  $\beta_{\text{HN},\beta}$ , and  $\tau_{0,\beta}$  obtained by fitting to the HN equation, we evaluated the distribution function  $F(s)$  of the relaxation time of the  $\beta$ -process for PMMA, where the subscript  $\beta$  means that these parameters are obtained for the  $\beta$ -process, and then we obtained the thickness dependence of FWHM  $w$ . The result of  $w$  is shown in Fig.8(a) (See open triangles). For the  $\beta$ -process of PMMA,  $w_0=4.7\pm0.2$  and  $a=3.20\pm0.02$  nm. In this figure, the result of  $w$  for the  $\alpha$ -process in PVAc is also shown instead of  $w$  for the  $\alpha$ -process in PMMA, because it was difficult to obtain  $w$  for the  $\alpha$ -process in PMMA. In addition to  $w$ , the normalized widths of the dielectric loss peak in the temperature domain due to the  $\alpha$ - and  $\beta$ -processes,  $\Delta T_i/\Delta T_i^0$  ( $i=\alpha, \beta$ ), are also shown in Fig.8(b). Because the relaxation time  $\tau$  is a function of the temperature  $T$ , the distribution function of relaxation times  $F(\log_e \tau)$  can be converted into that in the temperature domain, where the distribution function of the relaxation times with respect to temperature is given

by  $\tilde{F}(T) \equiv F(\log_e \tau(T)) \frac{d \log_e \tau}{dT}$ . Therefore, the distribution of the relaxation time can be evaluated not only from  $F(\log_e \tau)$  but also from the width in the temperature domain. Comparing these results with each other, we found that the distribution of the relaxation times of the  $\alpha$ -process becomes much broader with decreasing film thickness, while for the  $\beta$ -process this broadening is weaker or remains almost constant with decreasing film thickness.

Figure 5 shows the dependence of normalized relaxation strength on the reciprocal of film thickness for the  $\beta$ -process in thin films of PMMA (See open triangles). The relaxation strengths are obtained by fitting the observed frequency dependence of dielectric loss for the  $\beta$ -process at temperature at which the  $\beta$ -peaks are located at 300Hz. The dependence of normalized relaxation strength of the  $\alpha$ -process in thin films of PVAc with  $M_w=2.4\times10^5$  is also shown in Fig.5. However, that of the  $\alpha$ -process in PMMA has not yet been evaluated because the dielectric loss due to the  $\alpha$ -process in this case is much smaller than that due to the  $\beta$ -process. More precise and wider frequency range measurements will be required to extract the relaxation strength of the  $\alpha$ -process in PMMA especially in thinner films.

In Fig.5, it is found that the dielectric strengths of both the processes have a similar thickness dependence as follows:

$$\Delta\epsilon/\Delta\epsilon_{\text{bulk}} = 1 - \frac{\tilde{a}}{d}, \quad (6)$$

where  $\Delta\epsilon_{\text{bulk}}$  is the relaxation strength of the bulk sample, and  $\tilde{a}$  is a constant independent of  $d$ . The characteristic lengths fitted by Eq.(6) are  $13.8\pm0.3$  nm and  $6.5\pm0.3$  nm for the  $\alpha$ -process in PVAc and the  $\beta$ -process in PMMA, respectively

## IV. DISCUSSIONS

We have successfully observed many properties of dynamics of the  $\alpha$ -process in PVAc and the  $\alpha$ - and  $\beta$ -processes in PMMA. Here, we will discuss some of the results observed in this study.

### A. Thickness dependence of $T_\alpha$ in PVAc

In the case of PVAc, it has been observed that the temperature  $T_\alpha$  of the  $\alpha$ -peak in the temperature domain at 100Hz decreases with decreasing film thickness in a manner described by Eq.(1). The thickness dependence of  $T_\alpha$  has almost no  $M_w$  dependence in the  $M_w$  range from  $1.2\times10^5$  to  $2.4\times10^5$ .

In the case of the freely standing films of polystyrene, Mattsson *et al.* show that in a low  $M_w$  regime ( $M_w \leq 3.47\times10^5$ ) the value of  $T_g$  observed by Brillouin light scattering has no molecular weight dependence and

it decreases gradually with decreasing film thickness in a similar way to Eq.(1) [28]. On the other hand, in a high  $M_w$  regime ( $M_w \geq 5.14 \times 10^5$ ) the thickness dependence of  $T_g$  shows a distinct molecular weight dependence given by Eq.(2) and it depends on the radius of gyration of the polymer chain [28].

Although the existence of the interfacial interaction may lead to the difference in the  $d$  and  $M_w$  dependence of  $T_g$  between the freely standing films and the thin films supported on substrate, our recent study shows that the temperature  $T_\alpha$  observed at 100Hz and 1kHz by dielectric relaxation spectroscopy has a similar thickness and  $M_w$  dependence to Eq.(2) for thin PS films supported on Al-deposited glass substrate [17,18]. Therefore, it is expected that the thickness and  $M_w$  dependence of  $T_\alpha$  in thin films supported on substrate can be compared with that of  $T_g$  in freely standing thin films. For this reason, the observed results on  $T_\alpha$  in thin films of PVAc may correspond to the low  $M_w$  regime observed by Mattsson *et al.* in the freely standing films of PS. In the regime, *confinement effect of polymer chains* within thin films is not dominant for the reduction of  $T_g$  or  $T_\alpha$ , but *the finite size effects* due to a length scale intrinsic to the glass transition may be dominant. If we measure  $T_\alpha$  for thin films of PVAc with still higher molecular weights, however,  $M_w$  dependence of  $T_\alpha$  *vs.*  $d$  may be observed in a similar way to  $T_g$  in the freely standing films of PS.

## B. Thickness dependence of $T_\alpha$ and $T_\beta$ in PMMA

In PMMA, it can be expected that the characteristic length scale of the  $\beta$ -process, if any, should be smaller than that of the  $\alpha$ -process, because the characteristic time of the  $\beta$ -process at a fixed temperature in the temperature range investigated here is much shorter than that of the  $\alpha$ -process. In this case, the thickness dependence of  $T_\alpha$  should be stronger than that of  $T_\beta$  at a fixed frequency. However, the observed results do not obey this expectation; as shown in Fig.11, for  $d > d_{\alpha,c}$  ( $\approx d_{\beta,c}$ ),  $T_\alpha$  remains *almost independent of thickness* and  $T_\beta$  *decreases slightly with decreasing film thickness*.

According to a layer model, as discussed in the literature [12,18,29],  $T_g$  and the dynamics of thin films are controlled by the competition between the two different effects. Firstly, the existence of a mobile layer near surfaces leads to the speed-up of the dynamics of the  $\alpha$ -process (and also the  $\beta$ -process). Within the mobile layer molecular motions are enhanced compared with those in the bulk state. The origin of the enhancement of molecular motion is supposed to be due to the higher density of chain ends of polymer chains [30] or to the restriction on cooperative motions characteristic of the glass transition within the surface layer [28,31]. In the latter case, the layer thickness of the mobile layer is of an order of the size of the cooperatively rearranging region (CRR) [28]. Secondly, the attractive interaction between the polymers

and the substrate leads to slowing-down of the dynamics of the motion [32,33]. For example, the adsorption of polymer chains onto the substrate causes  $T_g$  of the thin films to increase compared with that in the bulk state.

In the case of thin films of PMMA, it has been reported that the glass transition temperature strongly depends on the interaction between the polymers and the substrate. Keddie *et al.* show that *the  $T_g$  increases with decreasing film thickness* for  $\text{SiO}_2$  substrate, while *it decreases with decreasing film thickness* for Au substrate [14]. Local thermal analysis measurements showed that  $T_g$  of thin films of PMMA supported on  $\text{SiO}_x$  is by 7K higher for  $d=20\text{nm}$  than that for the bulk films, while  $T_g$  on  $\text{SiO}_x$  with hexamethyldisilazane is by 10K lower for  $d=20\text{nm}$  [34]. In thin films of PMMA supported on Al deposited silicon substrate, it is reported that  $T_g$  of thin films with  $d=40\text{nm}$  is higher by  $14 \pm 4$  K than that of bulk PMMA [35]. These results suggest that the effect of the interaction between the polymer and the substrate is sensitive to the condition of the surface of the substrate in thin films of PMMA. In the  $\alpha$ -process in PMMA on Al-deposited substrate the mobile layer associated with cooperative length scale of the glass transition tends to reduce  $T_g$  and  $T_\alpha$ , while the attractive interaction between the polymer and the substrate tends to increase them. As a result, the two effects cancel out and the observed value of  $T_\alpha$  may *remain almost constant* for  $d > d_{\alpha,c}$ , as shown in Fig.11(a). For the  $\beta$ -process, it is expected that the two effects no longer cancel out and the mobile layer has dominant effect on  $T_\beta$ . In order to check the validity of the above idea, we should measure  $T_\alpha$  and  $T_\beta$  of PMMA thin films for a substrate which has almost no attractive interaction between the polymer and the substrate. In such a case, it is expected that as the thickness decreases  $T_\alpha$  decreases faster than  $T_\beta$  does.

In the present measurements, it is observed that for  $d < d_{\alpha,c}$  a drastic decrease in  $T_\alpha$  begins with decreasing film thickness. To our surprise,  $T_\beta$  also begins to decrease drastically with decreasing film thickness at almost the same film thickness  $d_{\beta,c}$  ( $\approx d_{\alpha,c}$ ). This indicates that there is a strong correlation between the  $\alpha$ -process and the  $\beta$ -process in PMMA thin films, although both the processes are located away from each other in the dispersion map (Fig.10). Both the values of  $d_{\alpha,c}$  and  $d_{\beta,c}$  agree well with the radius of gyration of the polymer chain ( $R_g \approx 18.6\text{nm}$ ), and hence this behavior may be controlled by the polymeric nature of PMMA.

The drastic change at  $d_{\alpha,c}$  implies the crossover from the normal  $\alpha$ -process to other type of dynamics. Recently, de Gennes proposed sliding motion, which can be activated via a soft skin layer near the surface instead of normal  $\alpha$ -dynamics [36,37]. Below  $d_c$ , the sliding motion may be activated in this case. The measurements of  $M_w$  dependence of  $T_\alpha$  and  $T_\beta$  for thin films of PMMA are highly desirable in order to clarify the nature of the above behavior on  $T_\alpha$  and  $T_\beta$ .

### C. Distribution of the relaxation times

The distribution of the relaxation times of the  $\alpha$ -process  $\tau_\alpha$  in thin films of PVAc has been found to become broader with decreasing film thickness. The width  $w$  of the distribution in PVAc with  $d=9.5\text{nm}$  is about 2.5 times as broad as that in bulk PVAc. On the other hand, the width  $w$  for the  $\beta$ -process in thin films of PMMA depends on film thickness much more weakly, as shown in Fig.8(a). The corresponding width  $\Delta T_i$  in temperature domain has a similar thickness dependence, *i.e.*, the thickness dependence of  $\Delta T_\beta$  is much weaker than that of  $\Delta T_\alpha$  in PMMA. From these observations, it is found that the distribution of relaxation times of the  $\alpha$ -process depends on film thickness much stronger than that of the  $\beta$ -process. The intrinsic length scale of the  $\beta$ -process is expected to be much smaller than that of the  $\alpha$ -process, as deduced from Fig.10. The present observation on the thickness dependence of the distribution of the relaxation times is consistent with this expectation.

### D. Thickness dependence of $\Delta\epsilon$

As shown in Fig.2, the dielectric loss peak due to the  $\alpha$ -process becomes more depressed with decreasing film thickness. This is consistent with the result that the relaxation strength  $\Delta\epsilon$  decreases with decreasing film thickness, as shown in Fig.5. The thickness dependence of  $\Delta\epsilon$  is found to obey Eq.(6). Here, we will try to give a possible explanation on the decrease in  $\Delta\epsilon$  with decreasing thickness.

If there is no interaction between dipole moments, the relaxation strength  $\Delta\epsilon_0$  is described as follows:

$$\Delta\epsilon_0 \approx \frac{N\mu_0^2}{3k_B T}, \quad (7)$$

where  $N$  is the dipole number density,  $\mu_0$  is the dipole moment of the relaxing unit,  $k_B$  is the Boltzmann constant, and  $T$  is the temperature. Now it is assumed that  *$n$  neighboring dipole moments are relaxed in a cooperative manner*. Then  $N$  and  $\mu_0$  should be replaced by  $N/n$  and  $n\mu_0$  in Eq.(7), respectively. As a result, we obtain the relaxation strength  $\Delta\epsilon_n$  for such a cooperative motion in the following way:

$$\Delta\epsilon_n \approx n \frac{N\mu_0^2}{3k_B T}. \quad (8)$$

Here, it can be expected that the number  $n$  is proportional to the intrinsic length of the motion in question. Because cooperative motions are restricted near surfaces or interfaces, the intrinsic length of the motions may be reduced and  $n$  is decreased. Therefore,  $\Delta\epsilon$  of the region near surfaces and interfaces can be expected to be smaller than that of the bulk system. By averaging along the direction normal to the film surface, the relaxation strength  $\Delta\epsilon$  is expressed by

$$\Delta\epsilon = \Delta\epsilon_{bulk} \left[ 1 - \xi \left( 1 - \frac{\Delta\epsilon_{surf}}{\Delta\epsilon_{bulk}} \right) \frac{1}{d} \right], \quad (9)$$

where  $\xi$  is the effective thickness of the surface region,  $d$  is the overall thickness, and  $\Delta\epsilon_{bulk}$  and  $\Delta\epsilon_{surf}$  are the relaxation strength of the bulk region and the surface regions, respectively. Here, the relation  $\Delta\epsilon_{bulk} > \Delta\epsilon_{surf}$  is satisfied. On the basis of this simple picture, the observed thickness dependence of  $\Delta\epsilon$  in Eq.(6) can be reproduced. The value of  $\tilde{a}$  is given by  $\tilde{a} = \xi(1 - \Delta\epsilon_{surf}/\Delta\epsilon_{bulk})$ . Therefore, the observed result on  $\Delta\epsilon$  in the present measurements is consistent with the idea of cooperative motions.

### V. SUMMARY

We made dielectric relaxation measurements for thin films of poly(vinyl acetate) and poly(methyl methacrylate) supported on Al deposited glass substrate. The results obtained in the present measurements are summarized as follows:

1. The temperature  $T_\alpha$  corresponding to the peak in the dielectric loss due to the  $\alpha$ -process at 100Hz is measured as a function of film thickness for thin films of PVAc with three different molecular weights  $M_w=1.2\times 10^5$ ,  $1.8\times 10^5$  and  $2.4\times 10^5$ . It is found that  $T_\alpha$  decreases gradually with decreasing film thickness and the decreasing rate of  $T_\alpha$  increases more and more in thinner films. Furthermore,  $T_\alpha$  has almost no molecular weight dependence.
2. The width of the distribution of the relaxation times of the  $\alpha$ -process increases with decreasing film thickness, while the relaxation strength of the  $\alpha$ -process decreases with decreasing film thickness.
3. The thickness dependence of the temperatures  $T_\alpha$  and  $T_\beta$  corresponding to the peaks in the dielectric loss due to the  $\alpha$ - and  $\beta$ -processes at 40Hz, respectively, are measured for thin films of PMMA with  $M_w=4.9\times 10^5$ . The temperature  $T_\alpha$  remains almost constant as the thickness is decreased down to a critical thickness  $d_{\alpha,c}$ , at which point it begins to decrease with thickness. The value of  $d_{\alpha,c}$  is about 20nm. On the other hand, the temperature  $T_\beta$  decreases slightly with decreasing film thickness from the bulk to a critical thickness  $d_{\beta,c}$ . Below  $d_{\beta,c}$   $T_\beta$  decreases more rapidly with decreasing film thickness. The value of  $d_{\beta,c}$  is almost equal to  $d_{\alpha,c}$ .
4. The widths  $\Delta T_\alpha$  and  $\Delta T_\beta$  of the peaks in dielectric loss in the temperature domain are measured for both the  $\alpha$ - and  $\beta$ -processes in thin films of PMMA with  $M_w=4.9\times 10^5$ . As the thickness is decreased, the width  $\Delta T_\alpha$  increases much faster than  $\Delta T_\beta$ . This indicates that the broadening of the distribution of relaxation times of the  $\alpha$ -process is much more sensitive to the change in thickness than that of the  $\beta$ -process.

In this paper, several length scales characteristic of the thickness change in  $T_\alpha$ ,  $\Delta T_\alpha$ ,  $T_\beta$ ,  $\Delta T_\beta$ ,  $\Delta\epsilon$ , and  $w$  have been introduced. The physical quantities such as  $\Delta T_\alpha$ ,  $\Delta T_\beta$ ,  $w$  and  $\Delta\epsilon$  have been found to be described by the linear equation of the reciprocal of  $d$ . This result suggests that a layer model be applicable to explain the thickness dependence, as shown in IV.D. In such cases, the characteristic lengths  $a$  and  $\tilde{a}$  are correlated with the thickness of the surface layer  $\xi$ , which can be expected to be comparable to the size of the CRR. On the other hand, the crossover thicknesses  $d_{\alpha,c}$  and  $d_{\beta,c}$  are almost equal to the radius of gyration of the polymer chain and are expected to be molecular weight dependent. These crossover thicknesses may be strongly associated with dynamics of polymer chains. In order to understand the present experimental results, a model will be required, where the nature of polymer dynamics is taken into account as well as the intrinsic nature of the glass transition.

## ACKNOWLEDGMENTS

The work was partly supported by a Grant-in-Aid from the Ministry of Education, Science, Sports and Culture of Japan.

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TABLE I. The weight averaged molecular weight  $M_w$ , the ratio of  $M_w$  to the number averaged molecular weight  $M_n$ , and radius of gyration of the polymers  $R_g$  used in this studies

|      | $M_w$   | $M_w/M_n$ | $R_g(\text{nm})^\dagger$ |
|------|---------|-----------|--------------------------|
| PVAc | 124,800 | 2.37      | 10.1                     |
|      | 182,000 | 2.95      | 12.2                     |
|      | 237,100 | 2.64      | 12.8                     |
| PMMA | 490,200 | 4.11      | 18.6                     |

<sup>†</sup> The values of  $R_g$  are obtained from Ref. [22].



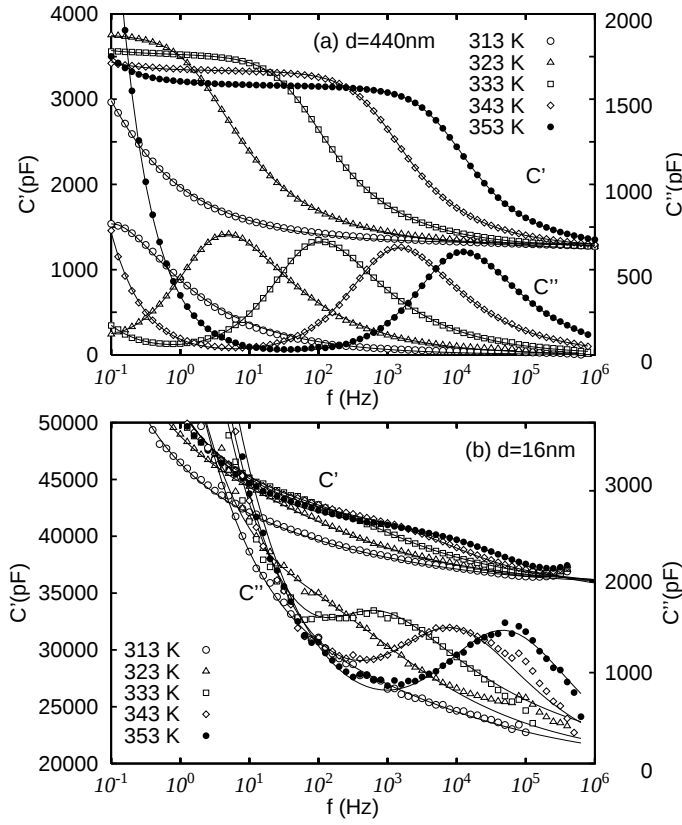


FIG. 1. The dependence of the complex electric capacitance on the logarithm of frequency at various temperatures for PVAc with  $M_w = 1.8 \times 10^5$ : (a)  $d=440\text{nm}$ , (b)  $d=16\text{nm}$ . Solid curves are calculated by Eq.(3).

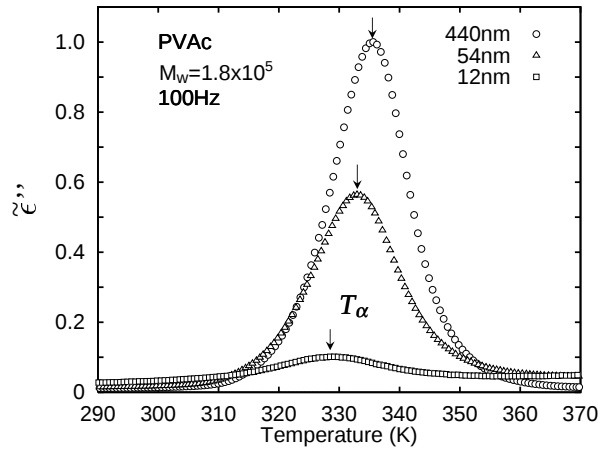


FIG. 2. The temperature dependence of the imaginary part of the complex dielectric constant at 100Hz for PVAc with  $M_w=1.8 \times 10^5$  and three different thicknesses:  $\circ$  corresponds to 440nm,  $\triangle$  to 54nm, and  $\square$  to 12nm. The value of the vertical axis is normalized with the maximum value for the bulk sample. The arrows indicate the values of  $T_\alpha$  at 100Hz.

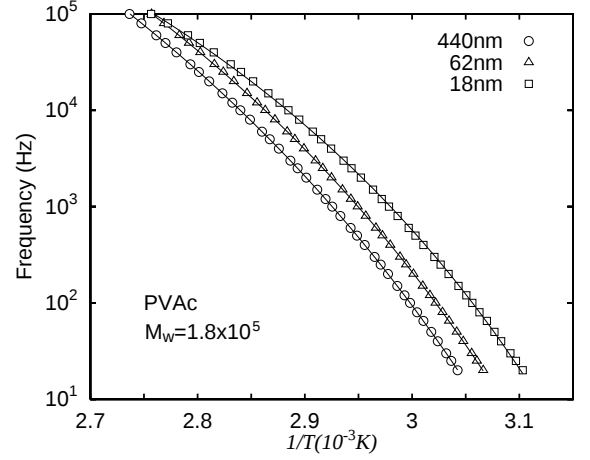


FIG. 3. The relationship between the temperature  $T_\alpha$  and the frequency  $f$  at which the dielectric loss possesses a maximum due to the  $\alpha$ -process for PVAc with  $M_w=1.8 \times 10^5$  and three different thicknesses:  $\circ$  corresponds to 440nm,  $\triangle$  to 62nm, and  $\square$  to 18nm. Solid curves are obtained by fitting the data to the VFT equation.

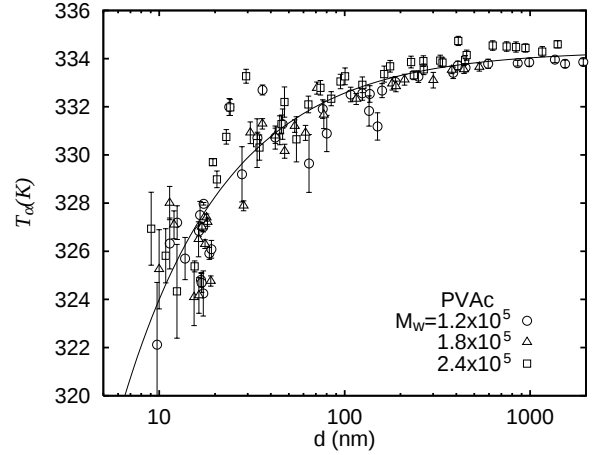


FIG. 4. Thickness dependence of the temperature  $T_\alpha$  for PVAc with three different molecular weights:  $\circ$  corresponds to  $M_w=1.2 \times 10^5$ ,  $\triangle$  to  $1.8 \times 10^5$ , and  $\square$  to  $2.4 \times 10^5$ . The temperature  $T_\alpha$  is a temperature at which the imaginary component of the complex dielectric constant possesses a maximum value at 100Hz.

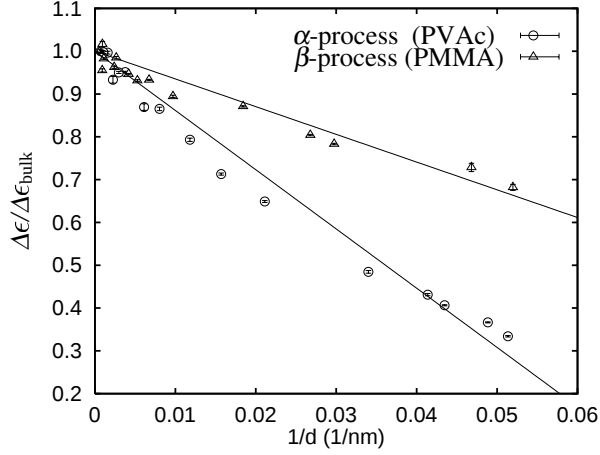


FIG. 5. Thickness dependence of the relaxation strength normalized with the value of the bulk sample. Open circles correspond to the result obtained at 333 K for the  $\alpha$ -process in PVAc with  $M_w=2.4 \times 10^5$  and open triangles to the result obtained at temperatures at which the dielectric loss peak is located at 300Hz for the  $\beta$ -process in PMMA with  $M_w=4.9 \times 10^5$ . Solid lines are obtained by Eq.(6). The characteristic lengths are  $13.84 \pm 0.34$  nm and  $6.48 \pm 0.31$  nm for the  $\alpha$ -process in PVAc and the  $\beta$ -process in PMMA, respectively

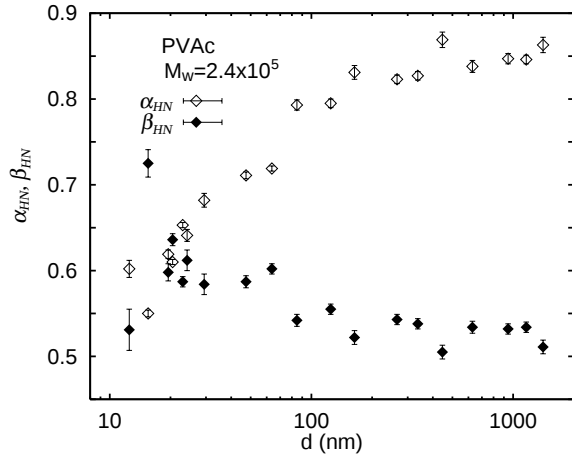


FIG. 6. The thickness dependence of the shape parameters  $\alpha_{HN}$  and  $\beta_{HN}$  of the HN equation obtained by fitting the observed data at 333K for PVAc with  $M_w=2.4 \times 10^5$ : open diamonds correspond to  $\alpha_{HN}$  and full diamonds to  $\beta_{HN}$ .

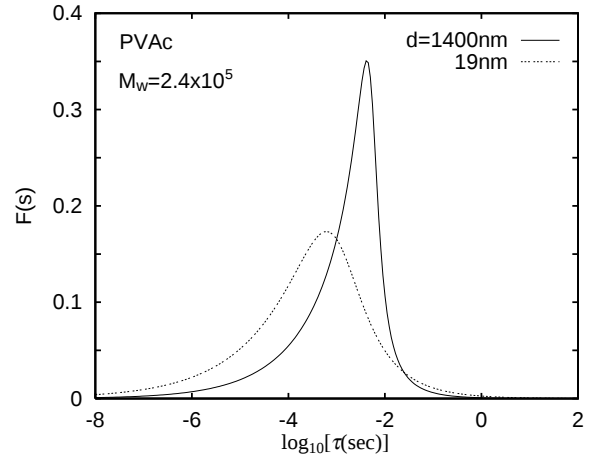


FIG. 7. The distribution function  $F(s)$  of the relaxation times of the  $\alpha$ -process at 333K for PVAc with  $M_w=2.4 \times 10^5$ . The values are calculated by Eq.(5) with the best-fit parameters of the HN equation. The solid curve stands for the result of  $d=1400$ nm and the dotted curve for that of  $d=19$ nm.

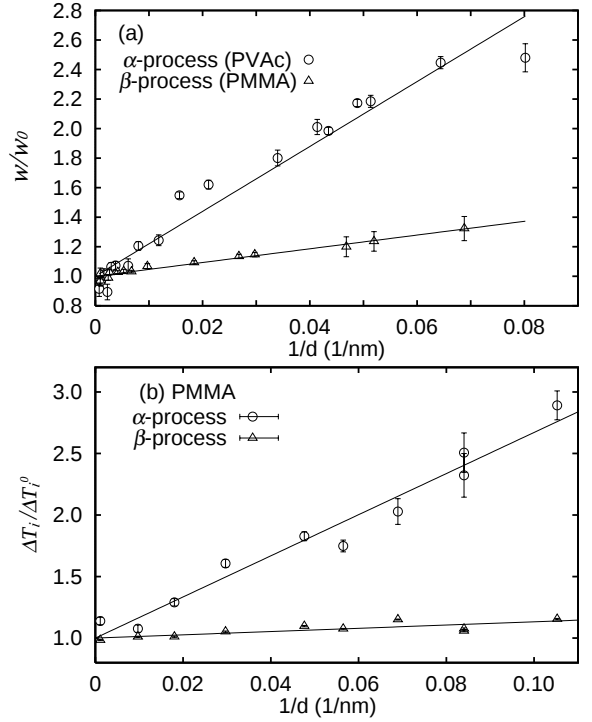


FIG. 8. (a) The thickness dependence of the normalized full width at the half maximum  $w/w_0$  for the  $\alpha$ -process in PVAc with  $M_w=2.4 \times 10^5$  ( $\circ$ ), and the  $\beta$  in PMMA with  $M_w=4.9 \times 10^5$  ( $\triangle$ ). The width for PVAc is evaluated at 333K and that for PMMA is at the temperature at which the  $\beta$ -peak in the dielectric loss is located at 300Hz. (b) The thickness dependence of the width  $\Delta T_\alpha$  and  $\Delta T_\beta$  of the  $\alpha$ -,  $\beta$ -peaks in the dielectric loss at 40Hz in the temperature domain. The width is normalized with that of the bulk sample.

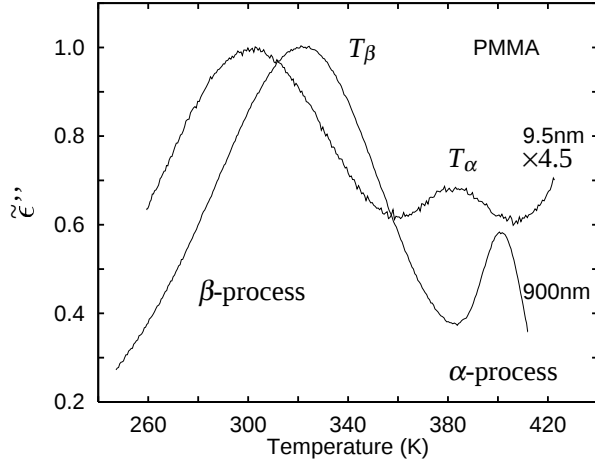


FIG. 9. The temperature dependence of the imaginary part of the complex dielectric constant at 40Hz for PMMA with the thickness of 9.5nm and 900nm. The vertical axis is normalized with the maximum value for the bulk sample. The value for  $d=9.5\text{nm}$  is magnified by a factor of 4.5.

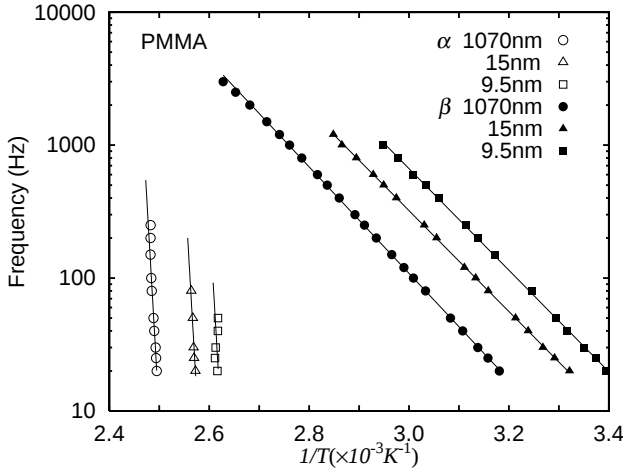


FIG. 10. Dispersion map of PMMA for various thicknesses. Circles correspond to  $d=1070\text{nm}$ , triangles to  $d=15\text{nm}$ , and boxes to  $d=9.5\text{nm}$ . Full and open symbols are for the  $\alpha$ -process and the  $\beta$ -process, respectively.

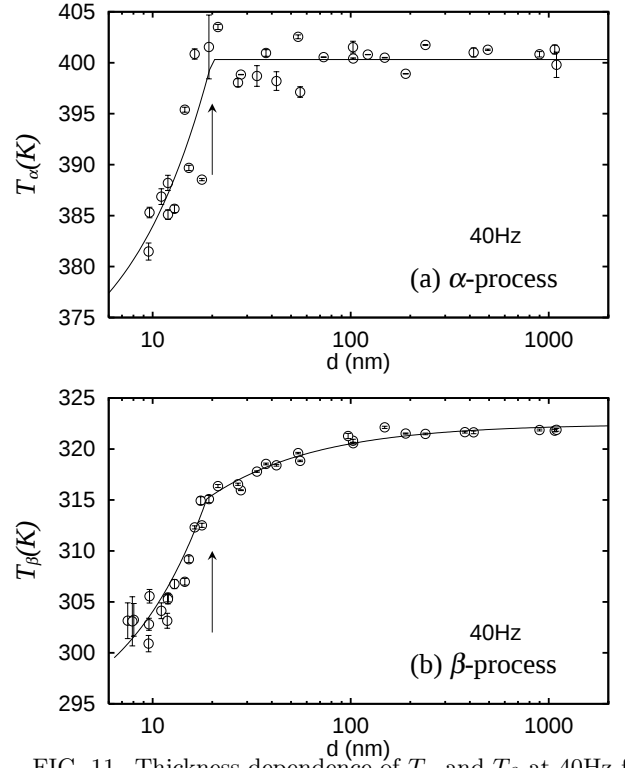


FIG. 11. Thickness dependence of  $T_\alpha$  and  $T_\beta$  at 40Hz for PMMA. The arrows indicate the critical thickness  $d_c$ .

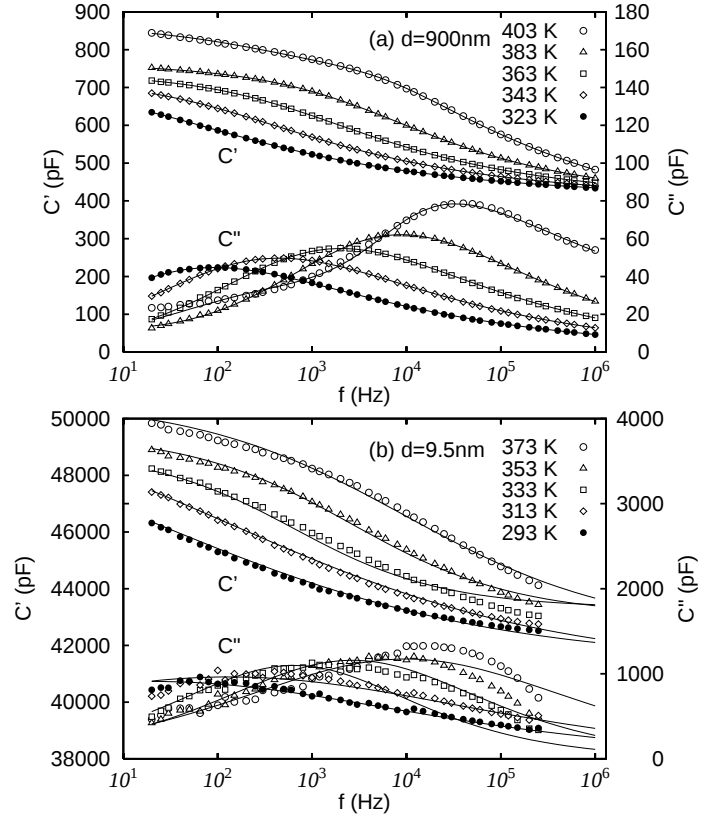


FIG. 12. The dependence of the complex electric capacitance on the logarithm of frequency at various temperatures for PMMA with  $M_w=4.9 \times 10^5$ : (a)  $d=900\text{nm}$ , (b)  $d=9.5\text{nm}$ . Solid curves are calculated by the sum of two HN equations.